



PATENT

PATENT
MP/RKK
10-2603
#12
Pke B
(alt)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Thomas H. Osterheld

Serial No.: 09/826,419

Filed: April 5, 2001

Confirmation No.: 5039

For: Grid Relief In CMP
Polishing Pad To
Accurately Measure Pad
Wear, Pad Profile And Pad
Wear Profile

Group Art Unit: 3723
Examiner: David
RE
01
TECHNO

Group Art Unit: 3723

Examiner: David B. Thomas

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TECHNOLOGY CENTER B3700

Box RCE
Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

CERTIFICATE UNDER 37 CFR 1.19

I hereby certify that this correspondence and the documents referred to as attached therein are being deposited on September 25, 2002 with the United States Postal Service in an envelope as "Express Mail Post Office to Addressee," mailing label No. EV186612760US addressed to: BOX RCE Commissioner for Patents, Washington, D.C. 20231.

9/25/02

Keith & Taks
Signature

Signature

PRELIMINARY AMENDMENT

Prior to continued examination, please enter the following amendments.

In the Claims:

Please cancel claims 1-4 and 14-20, and amend the claims as follows:

1. (Cancelled) A chemical mechanical polishing pad having a plurality of reliefs in a main polishing surface for determining wear of the pad, wherein the reliefs are disposed in a predetermined pattern such that the wear of the pad is determinable as a function of pad radius.